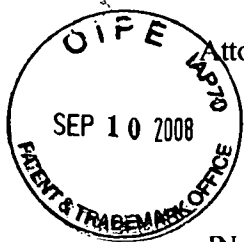


09-12-08

JF

AF



Attorney Docket No.: AM-8893 Y1

U.S. Express Mail No. EH 262355450 US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Ki-Ho Baik, et al.

§ GROUP ART UNIT: 1497

SERIAL NO.: 10/817,140

§

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RCE FILED: October 25, 2007

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§ EXAMINER: B.L. Raymond

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FOR: METHOD OF IMPROVING THE UNIFORMITY OF
A PATTERNED RESIST ON A PHOTOMASK

§

§ ATTORNEY DOCKET NO.:
§ AM-8893 Y1

Date: September 10, 2008

**RESPONSE "E" AFTER FINAL REJECTION
TRANSMITTAL LETTER**

Mail Stop AF
Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450


Sir:

The present Response "E" After Final Rejection is in reply to the Final Rejection mailed on July 10, 2008, having a shortened statutory period for response of October 10, 2008. Also attached herewith is a copy of a portion of the maintenance manual entitled, "Tetra II Photomask Etch Chamber" in Support of Declaration Under 37 C.F.R. §1.131. This Response is being filed within 2 months of the mailing date of the Final Rejection, entitling applicants to an advisory action.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. EH 262355450 US in an envelope addressed to: Mail Stop AF, Hon. Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Date: September 10, 2008


Shirley L. Church, Reg. No. 31,858